

## 1. (Amended)

*B2*  
*Sub*  
*C1* A method of manufacturing a thin film resistor with a moisture barrier comprising:  
depositing a metal film layer on a substrate;  
attaching a termination on each end of the metal film; and  
depositing a layer of tantalum pentoxide film directly overlaying and attaching to the metal film layer.

Please add new claim 15 as follows:

## 15. (New)

*B2*  
*Sub*  
*C2* A method of manufacturing a thin film resistor with a moisture barrier comprising:  
depositing a metal film layer on a substrate;  
attaching a termination on each end of the metal film;  
depositing a passivation layer directly overlaying and attaching to the metal film layer; and  
depositing a layer of tantalum pentoxide film directly overlaying and attaching to the passivation layer.